

2018 Okinawa Future Semiconductor Technical Committee

Date: 26th September, Wednesday PM1:00~PM17:20

Place: C209, Center building, Okinawa Institute of Science and Technology Graduate

Workshop Program@ C209, Center building

1:00~1:10 Prof. Baughman, Executive Vice President OIST, Opening Remarks

1:10~2:15 Dr. Hara (invited speaker),

Representative of Fab System Research Consortium, AIST

"Minimal Fab - using half-inch wafers to reduce a fab investment to 1/1,000"

2:15~2:45 Dr. Hirai, Director-General, AIST Kyushu,

"A Strategy of Minimal fab at AIST Kyushu

– Minimal IoT Device Prototyping Laboratory –"

2:45~3:10 Mr. Toonoe, Engineer, Yokogawa solution service,

" Minimal fab Introduction and Business Model of YOKOGAWA"

3:10~3:25 Break time & Networking

3:25~3:50 Dr Ogiso, Senior Researcher, AIST,

"Advantages and problems of small plasma generation technology"

3:50~4:15 Dr. Koizumi, Group leader, Wide Bandgap Semiconductors Group, NIMS,

"Recent topics in CVD diamond researches at NIMS"

4:15~4:40 Some company in Okinawa Prefecture

4:40~5:05 Prof. Fujii, N.I.T., Okinawa College,

" Diamond SAW filter fabricated by minimal-fab."

5:05~5:10 Prof. Fried, Closing Remarks